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PN - JP56025969 A 19810312

PD - 1981-03-12

PR - JP19790099762 19790804

OPD - 1979-08-04

TI - MANUFACTURE OF PRODUCT HAVING GLASSY FILM

IN - HATSUSHIRO MASAHIKO; YAMAKAWA SEISHIROU

PA - MATSUSHITA ELECTRIC WORKS LTD

- C03C17/25; C04B41/32; C23D5/00

O WPI / DERWENT

 Forming transparent glass coatings on substrates, e.g. metals - by applying aq. alkali metal silicate soln. and phosphate borate or aluminate baking and treating with hot water or steam

PR - JP19790099762 19790804

PN - JP56025969 A 19810312 DW 198118 000pp

- JP59049310B B 19841201 DW 198501 000pp

PA - (MATW) MATSUSHITA ELECTRIC WORKS LTD

IC - C03C17/25; C04B41/32; C23D5/00

- J56025969 Method comprises (1) applying an alkali metal silicate aq. solution containing (a) silicate of formula M 2O.xSiO 2.yH 2O (where M is alkali metal, x is at least 0.5, and y is 0 or positive number) and (b) at least one of phosphate, borate and aluminate of alkali metal an amount of 1-30 mol.% based in SiO 2 (calculated as P 2O5, B 2O3 or Al 2O3 respectively), (2) drying, (3) baking, (4) treating with hot water or steam.

- Pref. substrate is metallic plate (such as AI), glass plate or cement plate.
- Transparent, clear glassy coatings can be formed.

OPD - 1979-08-04

AN - 1981-31586D[18]

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HATSUSHIRO MASAHIKO; others: 01

PA - MATSUSHITA ELECTRIC WORKS LTD

TI - MANUFACTURE OF PRODUCT HAVING GLASSY FILM

PURPOSE:To manufacture products having transparent glassy coating, by mixing alkali metal silicate
of specific component with a specific salt of
ratio.

- CONSTITUTION:A material, shown by formula, comprising alkali metal silicate and a modifying agent contg. at least one member among phosphate, borate, and aluminate of 1a group alkali metal of the periodic table is used as the raw mterial. Said components in total 1-30mol in terms of respective P2O5, B 2O3, A 2O3 are mixed with 100mol SiO 2 component contained in glassy coating to prepare an aqueous soln. of modified alkali silicate. The aqueous soln is applied to a material, dried at < 100 deg.C temp., and baked primarily at 100-200 deg.C temp. and secondarily at 200-400 deg.C to form a film which is dealkalized with hot water and steam at >= 50 deg.C temp. for >= 0.5min respetively thereby producing a transparent glassy film.

- C23D5/00; C03C17/25; C04B41/32

none